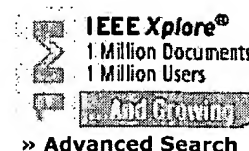




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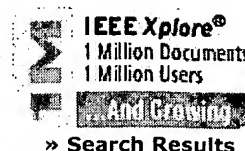
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#### 1 Semiclassical and wave mechanical modeling of charge control and direct tunneling leakage in MOS and H-MOS devices with ultra-thin oxides

*Cassan, E.; Dollfus, P.; Galdin, S.; Hesto, P.;*

Electron Devices, IEEE Transactions on, Volume: 48, Issue: 4, April 2001

Pages:715 - 721

[\[Abstract\]](#)   [\[PDF Full-Text \(160 KB\)\]](#)   IEEE JNL

#### 2 Gate leakage current simulation by Boltzmann transport equation and its dependence on the gate oxide thickness

*Zhiyi Han; Chung-Kai Lin; Goldsman, N.; Mayergoyz, I.; Yu, S.; Stettler, M.;*

Simulation of Semiconductor Processes and Devices, 1999. SISPAD '99. 1999

International Conference on, 6-8 Sept. 1999

Pages:247 - 250

[\[Abstract\]](#)   [\[PDF Full-Text \(320 KB\)\]](#)   IEEE CNF

#### 3 Junction leakage analysis using scanning capacitance microscopy

*Tarun, A.B.; Laniog, J.N.; Tan, J.M.; Cana, P.N.;*

Device and Materials Reliability, IEEE Transactions on, Volume: 4, Issue:

1, March 2004

Pages:46 - 49

[\[Abstract\]](#)   [\[PDF Full-Text \(360 KB\)\]](#)   IEEE JNL

#### 4 Degradation dynamics of ultrathin gate oxides subjected to electrical stress

*Miranda, E.; Cester, A.;*

Electron Device Letters, IEEE, Volume: 24, Issue: 9, Sept. 2003

Pages:604 - 606

[\[Abstract\]](#)   [\[PDF Full-Text \(239 KB\)\]](#)   IEEE JNL

#### 5 A model of radiation induced leakage current (RILC) in ultra-thin gate



Wettstein, A.; Schenk, A.; Fichtner, W.;  
Simulation of Semiconductor Processes and Devices, 1999. SISPAD '99. 1999  
International Conference on , 6-8 Sept. 1999  
Pages:243 - 246

[\[Abstract\]](#) [\[PDF Full-Text \(260 KB\)\]](#) **IEEE CNF**

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